

30. (Amended) A coated glass according to claim 21 wherein the coated glass has a normal emissivity of below 0.1.
31. (Amended) A coated glass according to claim 21 wherein the coated glass has been heat treated by heating it to a temperature in the range 400 to 700°C in an oxidising atmosphere.

Please delete claim 37.

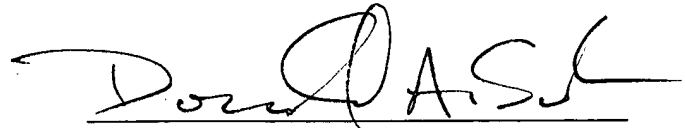
#### REMARKS

Applicant has amended the application to eliminate multiple dependencies and to adapt the claims to U.S. patent practice. A separate marked up copy of the amended claims is attached hereto entitled "Version With Markings To Show Changes Made".

Claims 3-8, 10, 12-13, 16-17, 19-20, 24-26, and 28-31 have been amended and claim 37 has been deleted. Claims 1-36 are currently pending in the present application. No new matter has been added by any of these amendments.

Favorable consideration of the application as amended is respectfully requested.

Respectfully submitted,

A handwritten signature in dark ink, appearing to read "Don DASH", written over a horizontal line.

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3. (Amended) A process according to [either] claim 1 [or claim 2] wherein the underlayer comprises a silicon oxide.
4. (Amended) A process according to [any one of claims 1-3] claim 1 wherein the underlayer comprises a silicon oxide containing carbon.
5. (Amended) A process according to [any one of claims 1-4] claim 1 wherein the pyrolytic deposition of the underlayer comprises contacting the glass substrate with a fluid mixture containing a silicon source, an oxygen source and a carbon source under conditions such that a silicon oxide layer, preferably containing carbon, is deposited.
6. (Amended) A process according to claim 5 wherein the fluid mixture is a [vapour] vapor mixture.
7. (Amended) A process according to [any one of claims 1-3] claim 1 wherein the underlayer comprises silicon oxide containing nitrogen.

8. (Amended) A process according to [any one of the preceding claims] claim 1 wherein the underlayer is deposited on the glass substrate when the glass substrate is at a temperature in the range 450°C to 800°C.
10. (Amended) A process according to [any one of preceding claims] claim 1 wherein the underlayer is deposited on to a glass ribbon during the float glass production process at substantially atmospheric pressure.
12. (Amended) A process according to [any one of the preceding claims] claim 1 wherein the reflective metal layer comprises silver or aluminium.
13. (Amended) A process according to [any one of the preceding claims] claim 1 wherein an anti-reflection layer is deposited by a vacuum deposition process on to the coated glass after deposition of the reflective metal layer.

16. (Amended) A process according to [any one of claims 13-15] claim 13 wherein a second reflective metal layer and a second anti-reflection layer are sequentially deposited by a vacuum deposition process after deposition of the first anti-reflection layer.
17. (Amended) A process according to [any one of the preceding claims] claim 1 additionally comprising a heat treatment step wherein the heat-treatable low emissivity coated glass is subjected to a temperature in the range 400 to 750°C in an oxidising atmosphere.
19. (Amended) A process according to [either] claim 17 [or claim 18] wherein the visible transmission of the coated glass is increased by the heat-treatment step.
20. (Amended) A coated glass produced by a process according to [any one of the preceding claims] claim 1.
24. (Amended) A coated glass according to [any one of claims 21-23] claim 21 wherein the underlayer has a refractive index in the range 1.5 to 3.

25. (Amended) A coated glass according to [any one of claims 21-24] claim 21 wherein the underlayer has a thickness in the range 30 to 100 nm.
26. (Amended) A coated glass according to [any one of claims 21-25] claim 21 wherein the reflective metal layer has a thickness in the range 5 to 30 nm.
28. (Amended) A coated glass according to [any one of claims 21-27] claim 21 wherein the anti-reflection layer has a thickness in the range 30 nm to 90 nm.
29. (Amended) A coated glass according to [any one of claims 21-28] claim 21 wherein the coated glass has a normal emissivity of below 0.2.
30. (Amended) A coated glass according to [any one of claims 21-29] claim 21 wherein the coated glass has a normal emissivity of below 0.1.

31. (Amended) A coated glass according to any one of claims 21-30] claim 21 wherein the coated glass has been heat treated by heating it to a temperature in the range 400 to 700°C in an oxidising atmosphere.

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